

## CLAIMS

1. A tank for producing arsenic vapor comprising a crucible located inside an exterior enclosure which isolates the crucible from the ambient atmosphere such that a space exists between the crucible and the exterior enclosure, the space being subjected to a pressure lower than atmospheric pressure, the crucible having an outlet duct and an input flange located at or adjacent a superheated portion of the crucible.
2. The tank according to claim 1, wherein the outlet duct and the flange are located in an essentially isothermal zone of the crucible.
3. The tank according to claim 1, wherein the vapor outlet duct is located in a half of the crucible of elevated temperature in which is located the input flange.
4. The tank according to claim 1, wherein the crucible comprises means for removable connection for maintenance of the duct on the enclosure.
5. The tank according to claim 1, wherein the enclosure has a condensation zone in the lower part of the tank and the condensation zone communicates with an input flange.
6. The tank according to claim 1, wherein the input flange is located in a horizontal plane at the end portion of a top part of the tank.

7. An epitaxy installation comprising an epitaxy enclosure communicating via a valve with the tank in accordance with claim 1, wherein the epitaxy enclosure and the tank are decouplably connected by a thermostated duct.

8. The epitaxy installation according to claim 7, wherein the tank is connected to the epitaxy enclosure via a duct having a positive temperature gradient.

9. The epitaxy installation according to claim 7, wherein a coupling axis between the enclosure and the tank is horizontal.

10. The epitaxy installation according to claim 7, wherein the duct is connected to the enclosure via a rotating connector.

11. The epitaxy installation according to claim 7, wherein a generatrix axis of the tank is essentially vertical.

12. The epitaxy installation according to claim 7, wherein a segment of a vapor outlet tube in the epitaxy enclosure is essentially perpendicular to an axis of the connection duct between the enclosure and the tank.

13. The epitaxy installation according to claim 7, wherein a segment of a vapor outlet tube in the epitaxy enclosure is inclined by about 40 to about 45° to permit connection with the inclined connection of the epitaxy enclosure.